

Patent Abstracts of Japan

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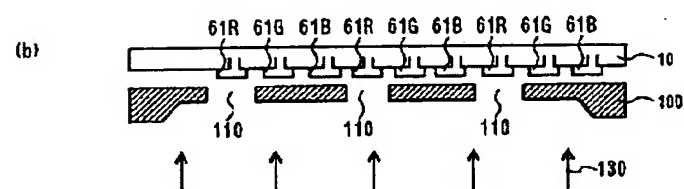
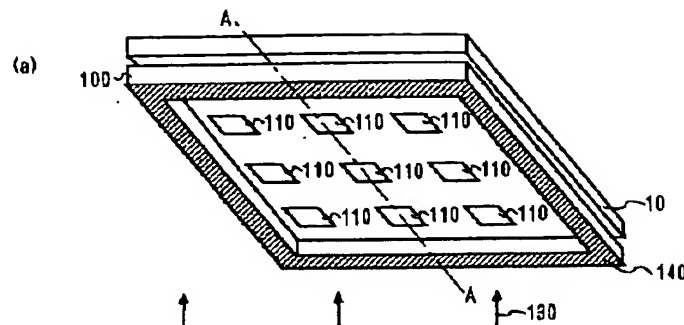
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TITLE : WORN MASK, ITS MANUFACTURING
METHOD, ELECTROLUMINESCENT
DISPLAY DEVICE AND ITS
MANUFACTURING METHOD



ABSTRACT : PROBLEM TO BE SOLVED: To provide an accurate mask to be worn and an EL display device wearing organic materials at given place with accuracy using the mask.

SOLUTION: SiO₂ film 101 is formed on a quadrangular shaped Si substrate 100, and with the SiO₂ film left around the substrate used as a mask, a mask area M and a step part 140 are formed by etching the Si substrate 100 with an etchant KOH, and then, the SiO₂ film is removed and a resist pattern 104 forming apertures 110 in the mask area M is formed and etching is done once again to form a mask to be worn. In so doing, an accurate mask made of Si substrate is obtained.

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